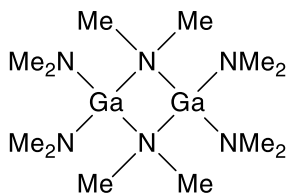


Catalog # 31-2030 Bis(μ -dimethylamino)tetrakis(dimethylamino)digallium, 98%

Thermal Behavior:

- Melting point: 90-91°C [1, 4]; 101-104°C [12]
- Sublimation: 70-72°C/1.5 Torr [2, 3], Sublimation rate 16.64×10^{-3} mg/min at 100°C [4]
- Decomposition: >125°C [4]
- TGA curves and data is available in [4, 12]

Technical Notes:

1. ALD/CVD precursor for gallium thin film deposition

Target Deposit	Deposition Technique	Delivery Temperature	Pressure	Co-reactants	Deposition Temperature	Ref.
Ga ₂ O ₃	ALD	70-72°C	1.5-2.2 Torr	H ₂ O	150-300°C	3
	CVD	60°C	0.75 Torr	O ₂	400-800°C	4
	PEALD	110°C		^{PL} O ₂	60-160°C	5
Er _x Ga _{2-x} O ₃	ALD	72°C	1.5-2.2 Torr	Er(CpMe) ₃ , H ₂ O	250-350°C	6
Sn _{1-x} Ga _x O _y	ALD	80°C	3.75 Torr	(Me ₂ N) ₄ Sn, H ₂ O	105-195°C	7, 8
GaS _x	ALD	100°C	0.01 Torr	H ₂ S	125-225°C	9, 10
Cu _x Ga _y S _z	ALD	72°C	0.75-3.75 Torr	Cu(acac) ₂ , H ₂ S	150°C	11
GaN	PEALD	<120°C	-	^{PL} NH ₃	150-400°C	12

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